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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/695,504	10/29/2003	Carsten Michaelsen	P8073US	8159
7590 05/02/2005		EXAMINER		
Kohler Schmid + Partner			HO, ALLEN C	
Ruppmannstr. 2 Stuttgart, D-7	7 9565		ART UNIT	PAPER NUMBER
GERMANY			2882	
			DATE MAILED: 05/02/2005	5

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	-
	10/695,504	MICHAELSEN ET AL.	
Office Action Summary	Examiner	Art Unit	_
	Allen C. Ho	2882	
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet	with the correspondence address	
	I V IC CET TO EVOIDE 21	MONTU(S) EDOM	
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR of after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a recommendation of the period for reply is specified above, the maximum statutory perions are reply within the set or extended period for reply will, by status Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	1. 1.136(a). In no event, however, may a ply within the statutory minimum of the d will apply and will expire SIX (6) MO ute, cause the application to become	a reply be timely filed nirty (30) days will be considered timely. DNTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on 29	October 2003.		
2a) This action is FINAL. 2b) ⊠ Th	nis action is non-final.		
3) Since this application is in condition for allow	ance except for formal ma	itters, prosecution as to the merits is	
closed in accordance with the practice under	Ex parte Quayle, 1935 C.	D. 11, 453 O.G. 213.	
Disposition of Claims			
4) Claim(s) 1-21 is/are pending in the application	on.		
4a) Of the above claim(s) is/are withdr	•		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>1-21</u> is/are rejected.			
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and	or election requirement.		
Application Papers			
9)⊠ The specification is objected to by the Examir	ner.		
10)⊠ The drawing(s) filed on <u>29 October 2003</u> is/ar		objected to by the Examiner.	
Applicant may not request that any objection to the	e drawing(s) be held in abey	ance. See 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the corre	ection is required if the drawir	g(s) is objected to. See 37 CFR 1.121(d).	
11) ☐ The oath or declaration is objected to by the I	Examiner. Note the attach	ed Office Action or form PTO-152.	
Priority under 35 U.S.C. § 119			
12)⊠ Acknowledgment is made of a claim for foreig	gn priority under 35 U.S.C.	§ 119(a)-(d) or (f).	
a)⊠ All b)□ Some * c)□ None of:			
1. Certified copies of the priority docume	nts have been received.		
2. Certified copies of the priority docume	nts have been received in	Application No	
3. Copies of the certified copies of the pr	iority documents have bee	n received in this National Stage	
application from the International Bure	au (PCT Rule 17.2(a)).		
* See the attached detailed Office action for a list	st of the certified copies no	ot received.	
Attachment(s)			
1) Notice of References Cited (PTO-892)		v Summary (PTO-413) o(s)/Mail Date	
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 		o(s)/ivialr Date f Informal Patent Application (PTO-152)	
Paper No(s)/Mail Date 102003, 112004.	6) Other:	·	

U.S. Patent and Trademark Office PTOL-326 (Rev. 1-04)

DETAILED ACTION

Drawings

1. The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, the continuously changing thickness of successive layers along the x-direction as claimed in claims 6-10 must be shown or the feature(s) canceled from the claim(s). No new matter should be entered.

Corrected drawing sheets in compliance with 37 CFR 1.121(d) are required in reply to the Office action to avoid abandonment of the application. Any amended replacement drawing sheet should include all of the figures appearing on the immediate prior version of the sheet, even if only one figure is being amended. The figure or figure number of an amended drawing should not be labeled as "amended." If a drawing figure is to be canceled, the appropriate figure must be removed from the replacement sheet, and where necessary, the remaining figures must be renumbered and appropriate changes made to the brief description of the several views of the drawings for consistency. Additional replacement sheets may be necessary to show the renumbering of the remaining figures. Each drawing sheet submitted after the filing date of an application must be labeled in the top margin as either "Replacement Sheet" or "New Sheet" pursuant to 37 CFR 1.121(d). If the changes are not accepted by the examiner, the applicant will be notified and informed of any required corrective action in the next Office action. The objection to the drawings will not be held in abeyance.

Specification

2. The disclosure is objected to because of the following informalities:

Page 19, line 17, "54" should be replaced by --55--.

Appropriate correction is required.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 4. Claims 1-5, 11, 12, and 15-21 are rejected under 35 U.S.C. 102(b) as being anticipated by Gutman et al. (U. S. Patent No. 6,014,423).

With regard to claim 1, Gutman et al. disclosed a reflector for x-ray radiation, the reflector comprising: means (12a, 18b) defining a first non-circular arc shape along a first cross section, the first cross section extending in an XZ plane containing an X direction; and means (12b, 18a) defining a second non-circular arc shape along a second cross section, the second cross section extending in a YZ plane perpendicular to the X direction (column 2, lines 32-41; column 3, lines 34-38).

Art Unit: 2882

With regard to claims 2 and 3, Gutman *et al.* disclosed the reflector of claim 1, wherein the second arc shape of the reflector along the second cross section defines focusing properties in the YZ plane (Figs. 1 and 4).

With regard to claim 4, Gutman *et al.* disclosed the reflector of claim 1, wherein the first and the second arc shapes focus or render parallel in two-dimensions (column 2, lines 32-41).

With regard to claim 5, Gutman *et al.* disclosed the reflector of claim 1, wherein the first arc shape is parabolic, hyperbolic, or elliptic along the first cross-section (column 2, lines 32-41).

With regard to claim 11, Gutman *et al.* disclosed the reflector of claim 1, wherein the second arc shape has an elliptic curvature of different lengths of semi-axes along the second cross-section (column 2, lines 32-41. This is the definition of an ellipse; otherwise it would be a circle).

With regard to claim 12, Gutman *et al.* disclosed the reflector of claim 1, wherein the second arc shape has a parabolic curvature along the second cross section (column 2, lines 32-41).

With regard to claim 15, Gutman *et al.* disclosed an x-ray analysis device comprising: an x-ray source (10); optical shaping and/or delimiting means (a collimator is required to operate a point x-ray source); and the reflector of claim 1.

With regard to claim 16, Gutman *et al.* disclosed the x-ray analysis device of claim 15, wherein x-ray radiation impinges on the reflector at an angle of less than 5° with respect to the x-direction (at glancing angle).

With regard to claim 17, Gutman et al. disclosed the x-ray analysis device of claim 15, wherein a curvature of the reflector along the second cross-section is formed such that a

reflectivity of the reflector is maximum for a wavelength of radiation generated by the x-ray source (This is simply Bragg diffraction. Column 3, lines 56-58).

With regard to claims 18 and 19, Gutman *et al.* disclosed the x-ray analysis device of claim 15, wherein the reflector focuses x-ray radiation to a focal spot (Figs. 1, 4).

With regard to claims 20 and 21, Gutman *et al.* disclosed the x-ray analysis device of claim 15, wherein the certain ray divergence generates parallel rays (column 2, lines 32-41).

5. Claims 1-3, 5-11, and 15-19 are rejected under 35 U.S.C. 102(b) as being anticipated by Hayashi et al. (U. S. Patent No. 6,249,566 B1).

With regard to claim 1, Hayashi *et al.* disclosed a reflector for x-ray radiation, the reflector comprising: means (40) defining a first non-circular arc shape along a first cross section, the first cross section extending in an XZ plane containing an X direction; and means (38) defining a second non-circular arc shape along a second cross section, the second cross section extending in a YZ plane perpendicular to the X direction (column 10, lines 45-46).

With regard to claims 2 and 3, Hayashi *et al.* disclosed the reflector of claim 1, wherein the second arc shape of the reflector along the second cross section defines focusing properties in the YZ plane (44).

With regard to claim 5, Hayashi *et al.* disclosed the reflector of claim 1, wherein the first arc shape is parabolic, hyperbolic, or elliptic along the first cross-section (column 10, lines 45-46).

With regard to claims 6-10, Hayashi et al. disclosed the reflector of claim 1, further comprising a periodically repeating sequence of layers of materials with different refractive indices, wherein a sum of thickness of successive layers of the materials change continuously

along the X-direction (column 11, line 29 - column 12, line 27), wherein the sum changes monotonically (last column in table 3).

With regard to claim 11, Hayashi *et al.* disclosed the reflector of claim 1, wherein the second arc shape has an elliptic curvature of different lengths of semi-axes along the second cross-section (This is the definition of an ellipse; otherwise it would be a circle).

With regard to claim 15, Hayashi *et al.* disclosed an x-ray analysis device comprising: an x-ray source (32); optical shaping and/or delimiting means (a collimator is required to operate a point x-ray source); and the reflector of claim 1.

With regard to claim 16, Hayashi *et al.* disclosed the x-ray analysis device of claim 15, wherein x-ray radiation impinges on the reflector at an angle of less than 5° with respect to the x-direction (at glancing angle).

With regard to claim 17, Hayashi *et al.* disclosed the x-ray analysis device of claim 15, wherein a curvature of the reflector along the second cross-section is formed such that a reflectivity of the reflector is maximum for a wavelength of radiation generated by the x-ray source (This is simply Bragg diffraction. column 2, lines 50 - column 3, line 11).

With regard to claims 18 and 19, Hayashi *et al.* disclosed the x-ray analysis device of claim 15, wherein the reflector focuses x-ray radiation to a focal spot (44).

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person

Application/Control Number: 10/695,504

Art Unit: 2882

having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Page 7

7. Claims 13 and 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Gutman et al. (U. S. Patent No. 6,014,423) or Hayashi et al. (U. S. Patent No. 6,249,566 B1) as applied to claim 1 above.

With regard to claims 13 and 14, Gutman et al. and Hayashi et al. disclosed the reflector of claim 1. However, Gutman et al. and Hayashi et al. failed to disclose that the reflector has a reflecting surface width of at least 4mm.

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to provide a reflecting surface width of at least 4mm, since a person would be motivated to provide a reflecting surface that is dimensioned to capture x-rays according to application requirement.

Conclusion

- 8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure:
 - (1) Hayashi *et al.* (U. S. Patent No. 6,823,042 B2) disclosed an apparatus for x-ray analysis.
 - (2) Antonell et al. (U. S. Patent No. 6,606,371 B2) disclosed an x-ray sytem.
 - (3) Taguchi et al. (U. S. Patent No. 6,529,578 B1) disclosed an x-ray condenser.
 - (4) Iwasaki *et al.* (U. S. Patent No. 6,504,902 B2) disclosed an x-ray optical device and multilayer mirror.

Application/Control Number: 10/695,504 Page 8

Art Unit: 2882

(5) Chen (U. S. Patent No. 6,317,483 B1) disclosed a doubly curved optical device

with graded atomic planes.

(6) Gutman et al. (U. S. Patent No. 6,041,099) disclosed a single corner Kirkpatric-

Baez beam conditioning optic assembly.

(7) Adema et al. (U. S. Patent No. 4,780,899) disclosed a crystal for x-ray analysis.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Allen C. Ho whose telephone number is (571) 272-2491. The

examiner can normally be reached on Monday - Friday from 8:00 am - 5:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Edward J. Glick can be reached at (571) 272-2490. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

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system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Allen C. Ho

Primary Examiner

allen C. Ho

Art Unit 2882